

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	16	("4410168" "4051010" "4752025" "4818838" "4972990" "5173338" "5474958" "6264185").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:24
S2	0	S1 and (electrochemical near2 machin\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 14:51
S3	0	S1 and ((electrolytic electrolytically) near2 machin\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 14:51
S4	3277	(electrochemical near2 machin\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 15:36
S5	15	(electrochemical near2 machin\$3) and 204/242.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 14:57
S6	5	(electrochemical near2 machin\$3) and 204/242.ccls. and ((negative adj pressure) (vacuum))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 14:58
S7	5	(electrochemical near2 machin\$3) and 204/242.ccls. and ((negative adj pressure) (vacuum)) and (lift remove separate move)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/19 19:02
S8	1	(electrochemical near2 machin\$3) and 204/242.ccls. and ((negative adj pressure) (vacuum)) and (lift remove separate move) and (piston)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 15:00

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S9	22	(electrochemical near2 machin\$3) and ((negative adj pressure) (vacuum)) and (lift remove separate move) and (piston)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/26 09:56
S10	284	(electrochemical near2 machin\$3) and ((negative adj pressure) (vacuum))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 15:07
S11	221	(electrochemical near2 machin\$3) and ((negative adj pressure) (vacuum)) and @ad<"20031222"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 15:08
S12	172	(electrochemical near2 machin\$3) and ((negative adj pressure) (vacuum)) and @ad<"20031222" and (lift move remove separate)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 15:08
S13	5	(electrochemical near2 machin\$3) and ((negative adj pressure) (vacuum)) and @ad<"20031222" and (lift move remove separate) and (positive adj pressure)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 15:55
S14	3	((electrochemical electrochemically electropolish\$2) near2 (machin\$3 polish\$3)) and ((negative adj pressure) (vacuum)) and @ad<"20031222" and (lift move remove separate) and (positive adj pressure) and (electrode)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 16:13
S15	1	((electrochemical electrochemically electropolish\$2) near2 (machin\$3 polish\$3)) and ((negative adj pressure) (vacuum)) and @ad<"20031222" and (lift move remove separate) and (positive adj pressure) and (electrode) and ((workpiece substrate) adj holder)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/26 10:08

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S16	1	((electrochemical electrochemically electropolish\$2) near2 (machin\$3 polish\$3)) and ((negative adj pressure) (vacuum)) and @ad<"20031222" and (lift move remove separate detach) and (positive adj pressure) and (electrode) and ((workpiece substrate) adj holder)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 16:23
S17	1265	(substrate workpiece) same (vacuum adj seal)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 16:22
S18	1	((electrochemical electrochemically electropolish\$2) near2 (machin\$3 polish\$3)) and S17	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 16:23
S19	1	S1 and electrode	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 16:49
S20	1986	(electrochemical near2 machin\$3) and @ad<"20031222"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 17:37
S21	736	(electrochemical near2 machin\$3).ti. and @ad<"20031222"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 17:39
S22	0	(electrochemical near2 machin\$3).ti. and @ad<"20031222" and ((create produce sustain maintain) with (vacuum suction (negative adj pressure)) with (seal\$3))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 17:41
S23	0	(electrochemical near2 machin\$3).ti. and @ad<"20031222" and ((create produce sustain maintain) same (vacuum suction (negative adj pressure)) same (seal\$3))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 17:42

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S24	2	(electrochemical near2 machin\$3).ti. and @ad<"20031222" and ((create produce sustain maintain) and (vacuum suction (negative adj pressure)) and (seal\$3))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 17:42
S25	24	(electrochemical near2 machin\$3).ti. and @ad<"20031222" and (vacuum suction (negative adj pressure))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 17:48
S26	8802	(vacuum adj chuck)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 17:48
S27	15	(vacuum adj chuck) and ((electrochemical adj machin\$3) (ECM))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 17:56
S28	4	(vacuum adj chuck) and ((electrochemical adj machin\$3) (ECM)) and ((substrate workpiece) adj holder)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 17:56
S29	17	204/297.03.ccls. and (semiconductor wafer microelectronic microfeature)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/22 10:12
S31	0	204/297.03.ccls. and (semiconductor wafer microelectronic microfeature) and piston	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/22 10:12
S32	5	204/297.03.ccls. and (semiconductor wafer microelectronic microfeature) and lift	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/26 10:10

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S33	2	204/297.03.ccls. and (semiconductor wafer microelectronic microfeature) and (positive adj pressure)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/22 10:50
S34	29	204/297.03.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 15:35
S35	3719	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:28
S36	8	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and (vacuum adj chuck)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/26 10:11
S37	316	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and (vacuum)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 15:42
S38	2172	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and @ad<"20030121"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 15:43
S39	4	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and @ad<"20030121" and (vacuum adj chuck)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 17:07
S41	124	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and @ad<"20030121" and (machining adj gap)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 15:49

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S42	17	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and @ad<"20030121" and (machining adj gap) and (surface near2 roughness)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:18
S43	0	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and @ad<"20030121" and (machining adj gap) and (degree near parallel\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:19
S44	2	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and @ad<"20030121" and (degree near parallel\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/26 10:17
S45	5	("4410168" "4051010" "4752025" "4818838" "4972990" "5173338" "5474958" "6264185").PN. and (parallel)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:24
S46	820	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and parallel	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:28
S47	826	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and parallel\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:28
S48	18	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and parallelism	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:36
S49	820	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and parallel	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:38

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S50	25	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and (resist\$4 near4 (anod\$4 (anod\$2 near2 (corrod\$2 corrosion))))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:40
S51	8	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and (resist\$4 near4 (anod\$4 (anod\$2 near2 (corrod\$2 corrosion)))) and titanium	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:40
S52	12	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and (resist\$4 near4 (anod\$4 (anod\$2 near2 (corrod\$2 corrosion)))) and (titanium ti)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:43
S53	177	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and ((anod\$4 (anod\$2 near2 (corrod\$2 corrosion)))) and (titanium ti)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:44
S54	10	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and (((anod\$4 (anod\$2 near2 (corrod\$2 corrosion)))) near4 (titanium ti))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:45
S55	2	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and (((anod\$4 (anod\$2 near2 (corrod\$2 corrosion)))) near4 (workpiece adj holder))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:46
S56	0	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and ((resistant resistance) near3 ((anod\$4 (anod\$2 near2 (corrod\$2 corrosion)))) near4 (workpiece adj holder))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:47
S57	0	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and ((resistant resistance) near3 ((anod\$4 (anod\$2 near2 (corrod\$2 corrosion)))) near4 ((workpiece substrate wafer) adj holder))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:47

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S58	0	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and ((resistant resistance resists) near3 ((anod\$4 (anod\$2 near2 (corrod\$2 corrosion)))) near4 ((workpiece substrate wafer) adj holder))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:48
S59	0	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and ((resistant resistance resist) near3 ((anod\$4 (anod\$2 near2 (corrod\$2 corrosion)))) near4 ((workpiece substrate wafer) adj holder))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:48
S60	1	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and (titanium ti) near4 ((workpiece substrate wafer) adj holder)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:49
S61	523	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and (titanium ti)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:50
S62	2	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and ((titanium ti) with holder)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:49
S63	64	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and ((titanium ti) and (corrosion near2 resist\$4))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:54
S64	21	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and ((titanium ti) with (corrosion near2 resist\$4))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:58
S65	2	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and ((titanium ti) with ((anode anodic) near2 corrosion))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/19 18:55

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S66	3	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and (resist\$4 near4 ((anode anodic) near2 corrosion))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 17:01
S67	0	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and ((resist\$4 near2 corrosion) with platen)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 17:02
S68	1	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and (Ti with platen)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 17:03
S69	13	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and (titanium with platen)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 17:03
S70	41	(vacuum adj chuck) same (roughness)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 17:08
S71	11	(electrochemical near2 machin\$3) and ((negative adj pressure) (vacuum)) and (lift remove separate move) and (piston) and @ad<"20030121"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/26 09:58
S72	4	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and (vacuum adj chuck) and @ad<"20030121"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/26 10:12
S73	3280	(electrochemical near2 machin\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/28 11:30

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S74	2	S73 and (resist with anod\$2 with corrosion)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/28 11:31
S75	19	S73 and (anod\$2 with corrosion)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/28 11:32
S76	3964	(resist\$4 with anod\$2 with corrosion)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/28 11:32
S77	939	(resist\$4 with anod\$2 with corrosion) and "204".clas.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/28 11:32
S78	2	"5556327".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/28 18:22
S79	2	"5870271".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/28 18:23
S80	24	("4410168" "4051010" "4752025" "4818838" "4972990" "5556327" "5870271" "5173338" "5474958" "6264185" "6416647" "6743349").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/15 15:24
S81	42338	((plenum (vacuum near (chamber plenum reservoir volume container space holding))) with (piston lift\$3 separat\$3 mount mount\$3 actuat\$3 rod bar))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/19 19:02

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S82	8	((plenum (vacuum near (chamber plenum reservoir volume container space holding))) with (piston lift\$3 separat\$3 mount mount\$3 actuat\$3 rod bar)) and (204/242,280.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/19 19:20
S83	9	((plenum (vacuum near (chamber plenum reservoir volume container space holding))) with (piston lift\$3 separat\$3 mount mount\$3 actuat\$3 rod bar eject eject\$3 pin)) and (204/242,280.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/19 19:23
S84	11	((plenum (vacuum near (chamber plenum reservoir volume container space holding chuck))) with (piston lift\$3 separat\$3 mount mount\$3 actuat\$3 rod bar eject eject\$3 pin)) and (204/242,280.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/19 20:31
S85	2045	((plenum (vacuum near (chamber plenum reservoir volume container space holding chuck))) with (piston lift\$3 separat\$3 mount mount\$3 actuat\$3 rod bar eject eject\$3 pin)) and (vacuum adj chuck) and (workpiece semiconductor microelectronic wafer substrate)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/19 20:34
S86	527	((plenum (vacuum near (chamber plenum reservoir volume container space holding chuck))) with (piston lift\$3 separat\$3 mount mount\$3 actuat\$3 rod bar eject eject\$3 pin)) and (vacuum adj chuck) and (workpiece semiconductor microelectronic wafer substrate) and (electrode anode cathode)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/19 20:35
S87	105	((plenum (vacuum near (chamber plenum reservoir volume container space holding chuck))) with (piston lift\$3 separat\$3 mount mount\$3 actuat\$3 rod bar eject eject\$3 pin)) and ((vacuum adj chuck).ti. (vacuum adj chuck).clm. (vacuum adj chuck).ab.) and (workpiece semiconductor microelectronic wafer substrate) and (electrode anode cathode)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/20 06:54
S88	1698	269/21.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/20 06:56

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S89	204	269/21.ccls. and ((plenum (vacuum near (chamber plenum reservoir volume container space holding chuck))) with (piston lift\$3 separat\$3 mount mount\$3 actuat\$3 rod bar eject eject\$3 pin))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/20 07:58
S90	14	269/21.ccls. and ((plenum (vacuum near (chamber plenum reservoir volume container space holding chuck))) with (piston lift\$3 separat\$3 mount mount\$3 actuat\$3 rod bar eject eject\$3 pin)) and (electrode anode cathode)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/20 08:12
S91	223	((plenum (vacuum near (chamber plenum reservoir volume container space holding chuck))) with (piston)) and (electrode anode cathode)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/20 08:14
S92	6	((plenum (vacuum near (chamber plenum reservoir volume container space holding chuck))) with (piston)) and (electrode anode cathode) and ((vacuum adj chuck). ti. (vacuum adj chuck).ab. (vacuum adj chuck).clm.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/20 08:15
S93	1	((plenum (vacuum near (chamber plenum reservoir volume container space holding chuck))) with (piston)) same (electrode anode cathode) and ((vacuum adj chuck). ti. (vacuum adj chuck).ab. (vacuum adj chuck).clm.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/20 08:15
S94	12	((plenum (vacuum near (chamber plenum reservoir volume container space holding chuck))) same (piston)) and (electrode anode cathode) and ((vacuum adj chuck). ti. (vacuum adj chuck).ab. (vacuum adj chuck).clm.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/20 08:16
S95	41	((plenum (vacuum near (chamber plenum reservoir volume container space holding chuck))) same (piston)) and (electrode anode cathode) and ((vacuum adj chuck)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/20 08:18

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S96	42	((plenum (vacuum near (chamber plenum reservoir volume container space holding chuck))) same (piston)) and (electrode anode cathode) and ((vacuum adj chuck) (vacuum near2 workholder))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/20 08:18
S99	1	269/21.ccls. and (vacuum adj chuck) and (reflectance transmittance) and (water)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/20 10:50
S10 2	8	269/21.ccls. and (vacuum adj chuck) and (reflectance transmittance optical) and ((clean clean\$3) with (surface wafer substrate))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/20 11:07
S10 4	991	(269/21.ccls. (vacuum adj chuck)) and (reflectance transmittance optical) and ((clean clean\$3) with (surface wafer substrate))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/20 11:11
S10 5	178	(269/21.ccls. (vacuum adj chuck)) and (reflectance transmittance optical) and ((clean clean\$3) with (surface wafer substrate) with water)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/20 11:11
S10 6	20	(269/21.ccls. (vacuum adj chuck)) and (reflectance transmittance spectroscopic) and ((clean clean\$3) with (surface wafer substrate) with water)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/20 11:14
S10 7	21	(269/21.ccls. (vacuum adj chuck) 356/244.ccls.) and (reflectance transmittance spectroscopic) and ((clean clean\$3) with (surface wafer substrate) with water)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/20 11:15
S10 8	1	(356/244.ccls.) and (reflectance transmittance spectroscopic) and ((clean clean\$3) with (surface wafer substrate) with water)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/20 11:19

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S10 9	3	(356/244.ccls.) and (reflectance transmittance spectroscopic) and ((clean clean\$3 rinse rins\$3) with (surface wafer substrate) with water)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/20 11:21
S11 0	3	(356/244.ccls.) and (spectrophotometer) and ((clean clean\$3 rinse rins\$3) with (surface wafer substrate) with water)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/20 11:29
S11 1	29	("356".clas.) and (spectrophotometer) and ((clean clean\$3 rinse rins\$3) with (surface wafer substrate) with water)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/20 11:30